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# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Robert L. Hodges, et al.      Art Unit:      Unassigned  
 Serial Number:      Unassigned      Examiner:      Unassigned  
 Filed:      HereWith  
 Title:      Semiconductor Device With Deposited Oxide  
 Date:      Jan. 18, 2002

Assistant Commissioner For Patents  
 Washington DC 20231

## PRELIMINARY AMENDMENT

Sir:

Please amend the above-identified patent application as follows:

### In the Specification:

Please delete paragraph 5.

Please replace paragraph 38 with the following paragraph. A marked-up version of paragraph 38 is enclosed herein.

--Cavitation barrier layer 142, barrier layer 158, and nozzle plate 160 define a firing chamber 148 having nozzle 150 providing an opening thereto. Electrical contact 144 is upon cavitation barrier layer 142. The ink jet print head seen in Figure 13 is in communication with a thermal ink jet printer 156 through a lead 154 to electrical contact 144. Figure 13 can be compared to Figure 6b in that gate electrodes 42 of Figure 6b are electrically isolated one from another by deposited oxide layer 44 there between which also prevents current from flowing between active region 38 of the first FET and active region 37 of the second FET. Similarly, gate electrode 120 of Figure 13 is electrically isolated from other gate electrodes by deposited oxide layers 118a, 118b on opposite sides of gate electrode 120. Such other gate electrodes